

Title (en)  
SUBSTRATE CLEANING APPARATUS AND METHOD

Title (de)  
VERFAHREN ZUR REINIGUNG VON EINEM SUBSTRAT UND EINRICHTUNG DAFÜR

Title (fr)  
APPAREIL ET PROCEDE DE NETTOYAGE DE SUBSTRAT

Publication  
**EP 1297566 A2 20030402 (EN)**

Application  
**EP 01944538 A 20010614**

Priority  
• US 0119218 W 20010614  
• US 59533600 A 20000614

Abstract (en)  
[origin: WO0197270A2] A substrate (30) may be cleaned by exposing the substrate (30) to an energized stripping gas while maintaining the substrate (30) at a first temperature and exposing the substrate (30) to an energized passivating gas while maintaining the substrate (30) at a second temperature. In another version, the substrate (30) is stripped and passivated in separate chambers. A cleaning chamber (120) may be provided with a heater (320) to heat the top of the substrate (30)

IPC 1-7  
**H01L 21/3213**; **H01J 37/32**

IPC 8 full level  
**G03F 7/42** (2006.01); **H01L 21/02** (2006.01); **H01L 21/027** (2006.01); **H01L 21/304** (2006.01); **H01L 21/306** (2006.01); **H01L 21/3065** (2006.01); **H01L 21/3213** (2006.01); **H01L 21/311** (2006.01)

CPC (source: EP)  
**G03F 7/427** (2013.01); **H01L 21/02071** (2013.01); **H01L 21/31138** (2013.01); **H01L 21/32136** (2013.01)

Citation (search report)  
See references of WO 0197270A2

Designated contracting state (EPC)  
DE FI FR GB IT NL

DOCDB simple family (publication)  
**WO 0197270 A2 20011220**; **WO 0197270 A3 20030123**; EP 1297566 A2 20030402; JP 2004514272 A 20040513

DOCDB simple family (application)  
**US 0119218 W 20010614**; EP 01944538 A 20010614; JP 2002511375 A 20010614